

### Abstract of the Disclosure

The invention relates to a diaphragm (1) for an integrator unit of a microlithographic projection exposure system. The diaphragm (1) includes a diaphragm opening (3), which is symmetrical with respect to a first axis of symmetry (5). The widths of the diaphragm aperture (3) in the direction of the axis of symmetry (5) are dependent on the distance ( $y$ ) from the first axis of symmetry (5). The widths are greater than or equal to the width at  $y = 0$ . The diaphragm (1), together with a cylindrical integrator, forms an integrator unit, which is located in an illumination system.